ABSTRACT

Lithographic Apparatus and Method

In an embodiment, a ring seal forming apparatus is disclosed, the apparatus including a substrate holder arranged to hold a substrate coated at least in part with resist, and a deep ultraviolet radiation outlet configured to irradiate an area of the resist, relative movement between the substrate holder and the deep ultraviolet radiation outlet being possible, the movement being arranged such that, in use of the apparatus, the area of resist irradiated by the deep ultraviolet radiation outlet is ring-shaped.